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Complete if Known Substitute for form 1449A/PTO **Application Number** 10/553,600 INFORMATION DISCLOSURE October 18, 2005 Filing Date Haruhiko KOMORIYA First Named Inventor STATEMENT BY APPLICANT Art Unit 1712 To Be Assigned **Examiner Name** (Use as many sheets as necessary) Attorney Docket Number 038788.56807US Sheet

Document Number	Publication Date	Name of Patentee or	Pages, Columns, Lines, Where
Number-Kind Code ² (if known)	MM-DD-YYYY	Applicant of Cited Document	Relevant Passages or Relevant Figures Appear
US- 3,036,091	05-22-1962	England	
		Number-Kind Code ² (if known)	Number-Kind Code ² (if known)

	FOREIGN PATENT DOCUMENTS						
Examiner Initials'	Cite	Foreign Patent Document Country Code ³ Number ⁴ Kind Code ⁶ (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	7⁰	
/N.C.	AB	WO 2004/014960 A2	02-19-2004	E. I. Dupont De Nemours and Company			
/N.C	AC	WO 02/36533 A1	05-10-2002	Daicel Chemical Industries, Ltd.		ABS	
/N.C	AD	JP 2003-55362 A	02-26-2003	Showa Denko Kabushiki Kalsha			
/N.C	AE /	JP 2003-2883 A	01-08-2003	Shin-Etsu Chemical Co., Ltd.			

NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²	
/N.C./	AF	DAMMEL et al., "New Resin Systems for 157nm Lithography", Journal of Photopolymer Science and Technology, 2001, Vol. 14, No. 4, pages 603 – 611.		
/N.C./	AG	FEDYNYSHYN et al., "Fluoroaromatic Resists for 157-nm Lithography", Journal of Photopolymer Science and Technology, 2002, Vol. 15, No. 4, pages 655 – 666.		
/N.C./	АН	International Search Report dated May 25, 2004 (Two (2) pages).		

Examiner	AND 100 1 1	Date	40/00/007
2. 1	/Nizal Chandrakumar/	Aal	12/20/2007
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